

REMARKS

Claims 1-11 are pending herein.

1. Claims 1 and 7-9 were rejected under 35 USC 103(a) as being unpatentable over Iijima et al. (5,650,378) or Iijima et al. (6,214,772) in combination with Savvides et al. (2004/0168636), Sioshansi et al. (5,236,509) or Maishev et al. (6,236,136) further in combination with Slaughter et al. (6,783,637). This rejection is respectfully traversed for the following reasons.

The claimed invention is drawn to a method of continuously coating at least one substrate with a buffer layer as a support for a ceramic superconducting material. The claimed invention particularly calls for feeding the at least one substrate across a substrate block within a deposition zone wherein a coating is applied to the at least one substrate while the at least one substrate is bombarded by ions from a dual RF-ion source along the deposition zone. Additionally, a separator is disposed within the deposition chamber and between the dual RF-ion sources, the separator being oriented along a direction that longitudinally bisects the substrate block and functioning to barricade impingement of ions from the first RF-ion source on the second portion and barricade impingement of ions from the second RF-ion source on the first portion. Iijima '378, Iijima '772, Savvides, Sioshansi, Maishev, and Slaughter fail to teach or suggest a separator disposed between the dual RF-ion sources, oriented along a direction that longitudinally bisects the substrate block, and functioning to barricade impingement of ions from the first RF-ion source on the second portion and barricade impingement of ions from the second RF-ion source on the first portion.

The attention of the PTO is drawn to the Rule 132 Declaration attached hereto. As explained in the declaration, stray ions from a first ion beam impinging on the second portion negatively impact the quality of the substrate. Applicants have discovered that the separator ensures good texture for the substrate segments within the deposition zone. Not only does the prior art fails to teach or suggest the use of a separator disposed between the dual RF-ion sources to prevent stray ions from a first RF-ion source from

impinging on the second portion and negatively impacting the quality of the substrate, but also fails to appreciate the significance of preventing stray ions from impinging on the substrate in a process where multiple RF-ion sources are used to increase the size of the deposition zone, and thus the number of substrate segments that can be processed concurrently.

Applicants submit that the PTO's reliance upon Iijima '378, Iijima '772, Savvides, Sioshansi, Maishev, and Slaughter is deficient. Accordingly, withdrawal of the rejections based on Iijima '378, Iijima '772, Savvides, Sioshansi, Maishev, and Slaughter is respectfully requested.

2. Claim 2 was rejected under 35 U.S.C. 103(a) as being unpatentable over Iijima et al. (5,650,378) or Iijima et al. (6,214,772) in combination with Savvides et al. (2004/0168636), Sioshansi et al. (5,236,509) or Maishev et al. (6,236,136) further in combination with Slaughter et al. (6,783,637) still further in combination with Fritzmeier et al. (6,797,313). Claims 3-6 were rejected under 35 U.S.C. 103(a) as being unpatentable over Iijima et al. (5,650,378) or Iijima et al. (6,214,772) in combination with Savvides et al. (2004/0168636), Sioshansi et al. (5,236,509) or Maishev et al. (6,236,136) further in combination with Slaughter et al. (6,783,637). Applicants respectfully submit the independent claims upon which these claims depend are in allowance. Accordingly, withdrawal of these rejections are respectfully requested.

Applicants respectfully submit that the present application is now in condition for allowance. Accordingly, the Examiner is requested to issue a Notice of Allowance for all pending claims.

Should the Examiner deem that any further action by the Applicants would be desirable for placing this application in even better condition for issue, the Examiner is requested to contact Applicants' undersigned attorney at the number listed below.

The Commissioner is hereby authorized to charge any fees which may be required, or credit any overpayment, to Deposit Account Number 50-3797.

Respectfully submitted,

Date

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David A. Schell, Reg. No.: 60,484

Agent for Applicant(s)

LARSON NEWMAN ABEL

POLANSKY & WHITE, LLP

5914 West Courtyard Drive, Suite 200

Austin, Texas 78730

(512) 439-7100 (phone)

(512) 439-7199 (fax)